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1 **Progress of Quantum Hall Research**  
2 **for Disseminating the Redefined SI**

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## 24 **Historical Context**

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## 25 **Basics of the Quantum Hall Effect**

26 To fully appreciate the impacts that the discovery of the quantum Hall effect (QHE)  
27 had on electrical metrology, it may benefit the reader to cultivate a general under-  
28 standing of the phenomenon (Von Klitzing and Ebert 1985; Von Klitzing et al. 1980).  
29 For the purposes of this handbook, a basic overview will be given. The QHE may be  
30 exhibited by a two-dimensional (2D) electron system when placed under a strong  
31 magnetic field perpendicular to the plane of the system. These conditions lead to  
32 quantization, or discrete energy states for charged particles in the magnetic field.  
33 These energy values, determined by solving the Schrödinger equation, are known as  
34 Landau levels. In precise measurements, one defines the quantized Hall resistance  
35  $R_{xy}$  as the measured voltage, perpendicular to the direction of the applied current,  
36 divided by that same current. The characteristic longitudinal resistivity  $\rho_{xx}$  goes to  
37 zero as  $R_{xy}$  approaches a quantized value over a range of magnetic field strength  
38 (nominally, a QHE plateau).

39 Since the discovery of the QHE at the start of the 1980s, the electrical metrology  
40 community has sought to implement a resistance standard based on the theoretical  
41 relation:  $R_H(\nu) = R_{xy}(\nu) = h/\nu e^2$ , where  $\nu$  is an integer related to the Landau energy  
42 level, and  $h$  and  $e$  are the Planck constant and elementary charge, respectively. In  
43 1990 the QHE was assigned a conventional value as an empirical standard based on  
44 the determination of fundamental constants through experiments such as the calcu-  
45 lable capacitor, which uses the Thompson-Lampard theorem (Thompson and  
46 Lampard 1956) to experimentally realize the unit of impedance, the farad, as defined  
47 by the International System of Units (SI). When the redefinition of the SI occurred in  
48 2019, the constants  $h$  and  $e$  were assigned globally agreed-upon exact SI values such  
49 that the electrical units of the ohm, volt, and ampere are defined by relation to these  
50 fundamental constants. Interestingly, the electrical quantum standards of resistance  
51 and voltage now realize the SI unit of mass, the kilogram, through the exact value of  
52  $h$  and an experiment called the Kibble Balance (Kibble 1976; Schlamminger and  
53 Haddad 2019). Within the redefined SI, many other fundamental constants are exact  
54 or have greatly reduced uncertainties (Tiesinga et al. 2021). For instance, the von  
55 Klitzing constant is now exact, calculated from  $h/e^2$  ( $R_K = 25\,812.807\,45 \dots \Omega$ ).

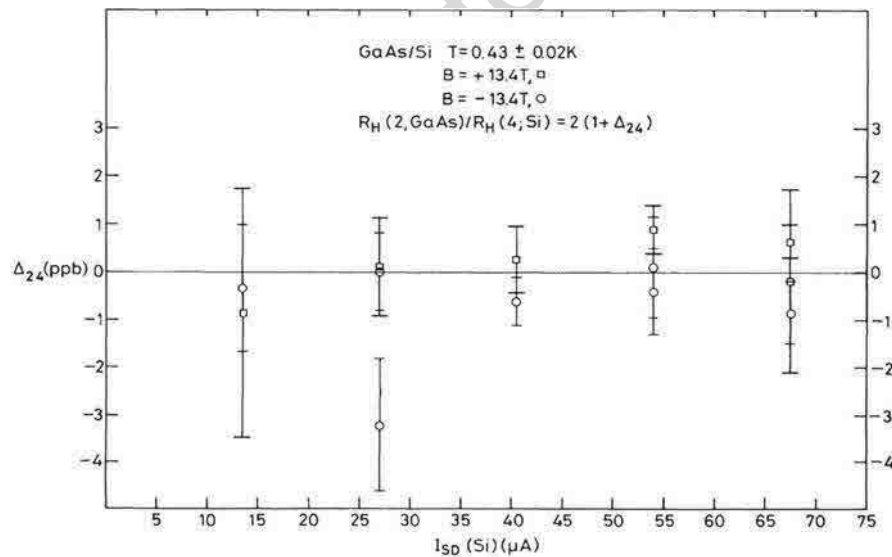
56 Before the QHE, resistance metrologists would employ standard resistors made  
57 from copper-manganese-nickel and similar stable alloys. These standards behaved  
58 differently in locations around the world due to variation of their nominal resistance  
59 (Witt 1998), and this robust, time-independant definition based on the ratio of  
60 fundamental constants has developed to allow expansion of the focus of the field.

## 61 **Predecessors for Quantum Hall Standards**

62 Quantum Hall standards began their journey shortly after the QHE was discovered.  
63 Some of the earliest devices were based on silicon metal–oxide–semiconductor field-  
64 effect transistors (MOSFETs). For Si systems, the electric field needed to define the

65 energy state of electrons in two dimensions was generated by a planar metallic  
 66 voltage gate separated from the surface of the semiconductor by an insulating oxide  
 67 layer. In work performed by Hartland et al., a cryogenic current-comparator (CCC)  
 68 bridge with a precise 1:1- or 2:1-ratio was used to compare two quantized Hall  
 69 resistances, one from the MOSFET and the other from a gallium arsenide (GaAs)  
 70 heterostructure, which employs layers of semiconductors to create a 2D quantum  
 71 well (Hartland et al. 1991). Both QHE devices were operated at the same tempera-  
 72 ture and magnetic field, but on different Landau levels. The critical components of  
 73 the CCC were immersed in liquid helium at 4.2 K and were shielded from external  
 74 magnetic fields using superconducting lead foil and low-temperature ferromagnetic  
 75 alloy (Hartland et al. 1991).

76 This work focused on comparing the quantized Hall resistance (QHR) of the  
 77 GaAs/AlGaAs heterostructure (measured at the  $\nu = 2$  plateau, or  $h/2e^2$ , which is  
 78 approximately 12.9 k $\Omega$ ) to that of the silicon MOSFET device (measured at the  $\nu = 4$   
 79 plateau, or  $h/4e^2$ , about 6.45 k $\Omega$ ). The deviations from the expected ratio of 2:1,  
 80 summarized in Fig. 1, are represented as  $\Delta_{24}$  and the ratio of the winding ratio allows  
 81 two resistances to be compared while canceling out the multiplicative factor of  
 82 2 between them. These results suggest that the two QHR values agree within 2  
 83  $[1 - 0.22(3.5) \times 10^{-10}]$ , where the uncertainty is in parentheses. Given the novelty of  
 84 the QHE at the time, this type of experiment was effective in supporting the notion of  
 85 representing the plateaus as based on the fundamental constants.



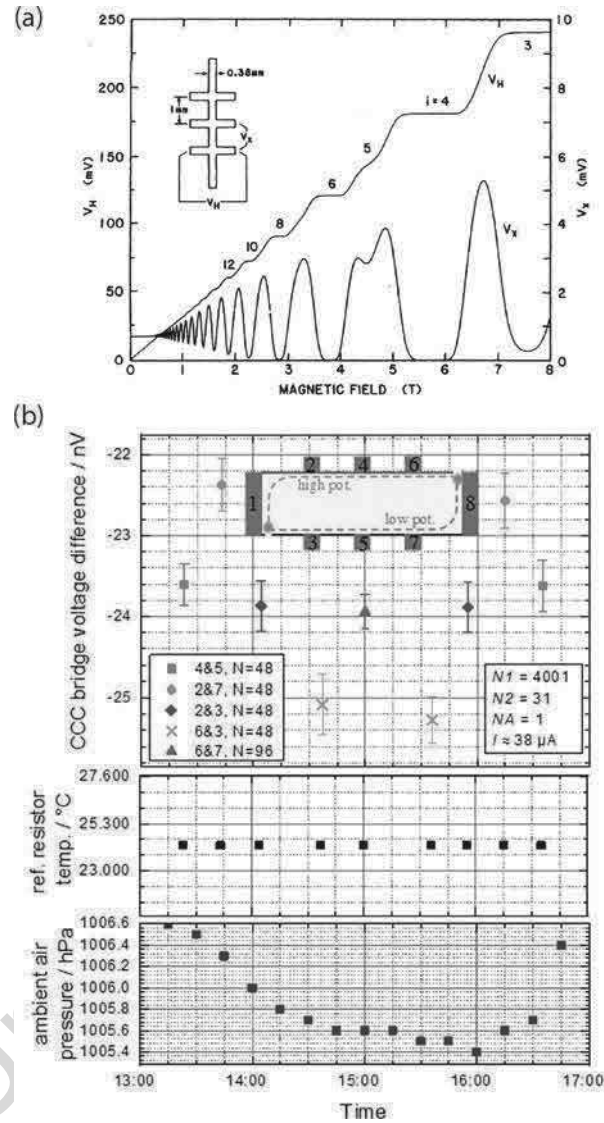
**Fig. 1** Measurements of  $\Delta_{24}$  expressed in parts per billion (ppb, or  $n\Omega/\Omega$ ) for the direct comparison of the GaAs-based device (at the  $\nu = 2$  plateau) and the Si MOSFET device (at the  $\nu = 4$  plateau). These data are shown as a function of the applied current through the Si MOSFET device, and the error bars represent a  $1\sigma$  random error of the average of  $\Delta_{24}$ . (Reprinted figure with permission from (Hartland et al. 1991). Copyright 1990 by the American Physical Society)

86 One of the disadvantages of MOSFETs was the high magnetic field required  
87 during an experiment. Laboratory magnetic fields of the time typically yielded a  
88 resistance plateau that was only quantized over a narrow range of magnetic field. As  
89 seen in (Hartland et al. 1991), the Si MOSFET device required 13 T to access its  $\nu =$   
90 4 plateau, and currents above 10  $\mu\text{A}$  would cause the QHE to break down, or lose its  
91 precise quantized value. These devices did not stay long in favor since GaAs-based  
92 devices quickly demonstrated more optimal behavior (Cage et al. 1985; Hartland  
93 1992). In GaAs-based devices, a 2D layer of electrons forms when an electric field  
94 forces electrons to the interface between two semiconductor layers (the other, in this  
95 case, being AlGaAs). For many devices with this type of interface, the layers were  
96 grown via molecular beam epitaxy (Tsui and Gossard 1981; Hartland et al. 1985).  
97 Similar heterostructures were developed in InGaAs/InP, which were obtained via  
98 metal-organic chemical vapor deposition (Delahaye et al. 1986).

99 These early GaAs-GaAlAs heterostructure devices were grown with excellent  
100 homogeneity and exhibited high mobilities (on the order of  $200\,000\text{ cm}^2\text{V}^{-1}\text{s}^{-1}$ ) at  
101 4 K. The success of this material in providing highly precise quantized resistances  
102 led in 1990 to the definition of the  $R_{\text{K}-90}$  representation of the ohm as recommended  
103 by the Consultative Committee for Electricity (CCE) (Taylor 1990). For another  
104 20 years, technologies continued to improve, allowing both GaAs-based resistance  
105 standards and cryogenic measurement methods to offer increased sensitivity and  
106 precision (Jeckelmann et al. 1997; Williams 2011).

107 During the 1980s, metrologists at national metrology institutes (NMIs) utilized  
108 these high-quality devices to confirm the universality of the von Klitzing constant  $R_{\text{K}}$   
109 over the course of many experiments. An example of the use of GaAs-based devices  
110 for metrology can be seen in Cage et al. (1985), where the authors looked to adopt  
111 GaAs as a standard used to maintain a laboratory unit of resistance. The work again  
112 demonstrated the universality of the QHE and showed the viability of the device as a  
113 means to calibrate artifact standards. The devices were grown by molecular beam  
114 epitaxy at an AT&T Bell Laboratory facility in New Jersey (Cage et al. 1985) and  
115 had dimensions as shown in the inset of Fig. 2. The magnetic field sweep data for the  
116 Hall and longitudinal voltages are also shown in Fig. 2a. The second part of the  
117 experiment involved transferring the QHE value through 1:1 comparisons to a set of  
118  $6453.2\ \Omega$  resistors, and from there to the US ohm, maintained with a group of  
119 resistors at the  $1\ \Omega$  level (Hamon 1954). Comparisons were done using a direct  
120 current comparator (DCC) resistance bridge and reconfigurable series-parallel resis-  
121 tor networks at several resistance levels (Cage et al. 1985).

122 Before a QHR device can be utilized for calibration, it needs to pass a character-  
123 ization procedure. The main purpose here is to identify instabilities over time as well  
124 as asymmetries in the device properties for different combinations of contacts. The  
125 systematic series of CCC measurements shown in Fig. 2b involves various combi-  
126 nations of orthogonally and diagonally aligned pairs of Hall contacts inside the  
127 device. It is performed at the same fixed  $B$ -field intended to be later used for the  
128 calibration procedure in which the QHR will be the reference. The suitable  $B$ -field,  
129 where the deviation from  $R_{\text{K}}/2$  is expected to be on the level of  $1\ \text{n}\Omega/\Omega$ , is typically  
130 identified prior to this procedure by characterizing the longitudinal resistivity  $\rho_{\text{xx}}$  at  
131 several points within the resistance plateau.



**Fig. 2** (a) Hall and longitudinal voltage measurements from a magnetic field sweep of a GaAs-based device. The temperature was 1.2 K and the applied current was 25.5  $\mu\text{A}$ . © 1985 IEEE. Reprinted, with permission, from (Cage et al. 1985). (b) A practical example of the final high accuracy device characterization procedure prior to calibration at a fixed  $B$ -field where the deviation from  $R_K/2$  is expected to be below 1  $\text{n}\Omega/\Omega$ . The characterization procedure of the device (CCC bridge voltage difference) involves a series of CCC measurements at diagonally and orthogonally aligned Hall contact pairs with the primary purpose of identifying instabilities over time as well as asymmetries in the device properties. The quantity  $N$  describes the number of measurement cycles in the CCC measurement. The error bars represent type A expanded measurement uncertainties ( $k = 2$ ). To identify instabilities related to the room-temperature reference resistor, the ambient air pressure and the reference resistor temperature are recorded simultaneously as one characterizes the QHR device

132 A series of eight symmetrically arranged Hall measurements at five pairs of Hall  
133 contacts (see inset in Fig. 2b) are applied in the following order: (1) contacts 4 and  
134 5, (2) contacts 2 and 7, (3) contacts 2 and 3, (4) contacts 6 and 3, (5) contacts 6 and  
135 7, (6) contacts 2 and 3, (7) contacts 2 and 7, (8) contacts 4 and 5. Whereas the contact  
136 pairs 2 and 7 (and 6 and 3) are diagonally aligned and thus have a longitudinal  
137 resistance component, the other contact pairs 4 and 5, 2 and 3, and 6 and 7 are  
138 orthogonally aligned Hall contacts. Therefore, in the case where a device exhibits  
139 equal quantization in all regions, the Hall resistances and corresponding bridge  
140 voltages at the Hall contact pairs 4 and 5, 2 and 3, and 6 and 7 should be the same  
141 within the expanded uncertainties. Since the remaining contact pairs 2 and 7 (and  
142 6 and 3) have a longitudinal component across the full accessible length of the  
143 device, they should deviate from the previous three pairs according to their longitu-  
144 dinal resistance component. The results of the practical example, plotted in Fig. 2b,  
145 represent a typical pattern of such a measurement series. The difference voltage in  
146 nV represents average data derived using a CCC in a series of current-reversed  
147 measurements. The measured bridge voltage difference can be used to calculate the  
148 value of the unknown resistor if the reference resistor value, winding ratio, and  
149 compensation network configuration are known quantities (Götz et al. 2009).

150 In the case of instabilities in the QHR device or the reference resistor, the  
151 measurement results can be asymmetrically distributed or not be reproducible over  
152 time within the expanded uncertainties. Additionally, the noise and uncertainty  
153 figures of the individual measurements should be similar for all pairs of contacts.  
154 A typical expanded ( $k = 2$ ) type A uncertainty of a CCC bridge voltage in a QHR  
155 versus a  $100 \Omega$  measurement is below  $0.5 \text{ nV}$  after 48 measurement cycles. To be  
156 able to identify instabilities caused by the reference resistor, it is recommended to  
157 simultaneously record the ambient pressure and resistor temperature during the  
158 measurement as shown in the bottom panels of Fig. 2b. The final dc calibration  
159 procedure in which the QHR is used as a reference is typically realized by using the  
160 center Hall contact pair 4 and 5.

## 161 **Expansion of QHR Device Capabilities**

162 QHR devices soon became the norm in the electrical metrology community, with  
163 many of the NMI efforts implementing the new standards based on GaAs devices  
164 (Small et al. 1989; Cage et al. 1989; Delahaye and Jeckelmann 2003; Jeckelmann  
165 and Jeanneret 2001). Compared to the part-per-million or larger changes that  
166 occurred over the years before 1990 in many NMI ohm representations based on  
167 standard resistors, better agreement was obtained (by an order of magnitude)  
168 between the various worldwide NMIs in later resistance intercomparisons. However,  
169 to calibrate standards at resistance levels far removed from the QHR value, several  
170 stages of resistance ratio scaling were required and the uncertainty increased with  
171 each stage. The next natural step for metrologists was to examine whether or not  
172 these QHR devices could accommodate other values of resistance so that the  
173 calibration chain could be shortened. More advanced experiments and models

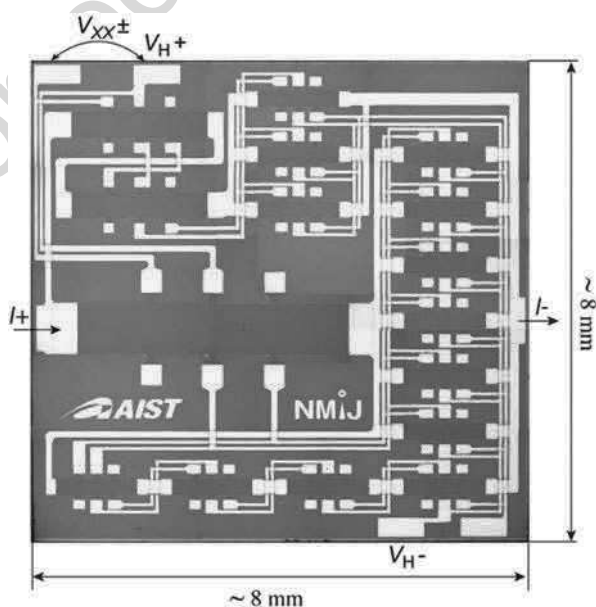


174 were developed by studies of QHE behavior and showed how this may be accom-  
 175 plished by constructing quantum Hall array resistance standards (QHARS) (Oe et al.  
 176 2013; Poirier et al. 2004; Ortolano et al. 2014; Konemann et al. 2011).

177 For instance, in Oe et al., a 10 k $\Omega$  QHARS device was designed and consisted of  
 178 16 Hall bars, providing a more easily accessible decade resistance value compared to  
 179 previous work (Oe et al. 2013). The nominal value of the device was about 34 n $\Omega/\Omega$   
 180 from 10 k $\Omega$  (based on  $R_{K-90}$ ). The design and final device can be seen in Fig. 3. The  
 181 device was measured using a CCC to compare the device against an artifact  
 182 calibrated using another well-characterized QHR device. In this case, a 100  $\Omega$   
 183 standard resistor was used to verify that the array device agreed with its nominal  
 184 value to within approximately one part in  $10^8$ . The work also proposed new  
 185 combinations of Hall bars such that the array output could be customized for any  
 186 of the decade values between 100  $\Omega$  and 1 M $\Omega$  (Oe et al. 2013).

187 In addition to the benefits gained from expanding GaAs-based devices further  
 188 into the world of metrology using direct current (DC), expansion was also explored  
 189 in the realm of alternating current (AC). Various NMIs began standardizing imped-  
 190 ance by using the QHE in an effort to replace the calculable capacitor, which is a  
 191 difficult apparatus to construct and time-consuming to operate (Ahlers et al. 2009;  
 192 Cabiati et al. 1999; Bykov et al. 2005; Hartland et al. 1995; Wood et al. 1997). The  
 193 QHE still exhibited plateaus even at very high excitation frequencies, as shown in  
 194 Bykov et al., which described the behavior of the 2D electron system in GaAs-based  
 195 devices for frequencies between 10 KHz and 20 GHz (Bykov et al. 2005). However,  
 196 when the applied current was AC, a new set of oscillations dependent on the

**Fig. 3** A 10 k $\Omega$  QHARS device is shown with 16 Hall bars. The chip has lateral dimensions of 8 mm per side and was fabricated to be mounted on a standard transistor outline (TO)-8 package. The contact pads are labeled based on whether they are used for current injection or voltage measurements. (© 2013 IEEE. Reprinted, with permission, from (Oe et al. 2013))



197 magnetic field was found. This is relevant for impedance metrology because having  
198 a longitudinal resistance very close to zero is one mark of a well-quantized device,  
199 and having AC frequency-dependent oscillations would undoubtedly increase the  
200 uncertainty associated with the QHR. Challenges in adopting QHR technology still  
201 exist today in this branch of electrical metrology.

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## 202 **The Graphene Era Begins**

### 203 **Comparing Graphene to GaAs**

204 At the end of the 2000s, research in 2D materials like graphene became prevalent  
205 (Zhang et al. 2005; Novoselov et al. 2005, 2007; De Heer et al. 2007). It was evident  
206 that QHR measurements could be graphene-based, with fabrications performed by  
207 chemical vapor deposition (CVD) (Jabakhanji et al. 2014), epitaxial growth  
208 (De Heer et al. 2007; Janssen et al. 2012), and the exfoliation of graphite (Giesbers  
209 et al. 2008). Given the many methods of available graphene synthesis, efforts to find  
210 an optimal synthesis method for metrological purposes were underway. Exfoliated  
211 graphene was widely known to exhibit the highest mobilities due to its pristine  
212 crystallinity. It was a primary initial candidate as far as metrological testing was  
213 concerned. It was found in Giesbers et al. that devices constructed from flakes of  
214 graphene had low breakdown currents relative to GaAs-based counterparts, with  
215 currents on the order of 1  $\mu\text{A}$  being the maximum one could apply before observing a  
216 breakdown in the QHE (Giesbers et al. 2008) (Fig. 4).

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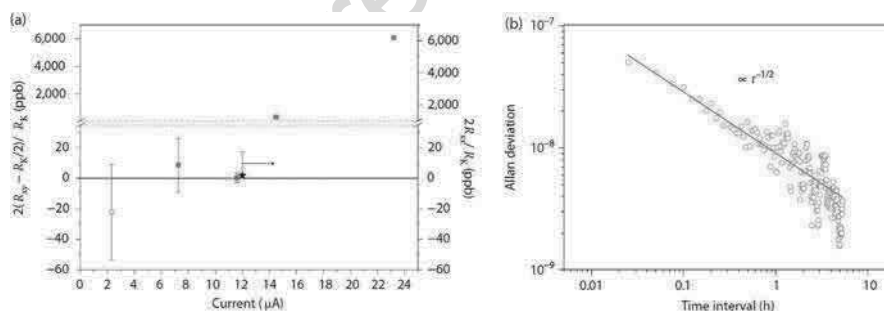
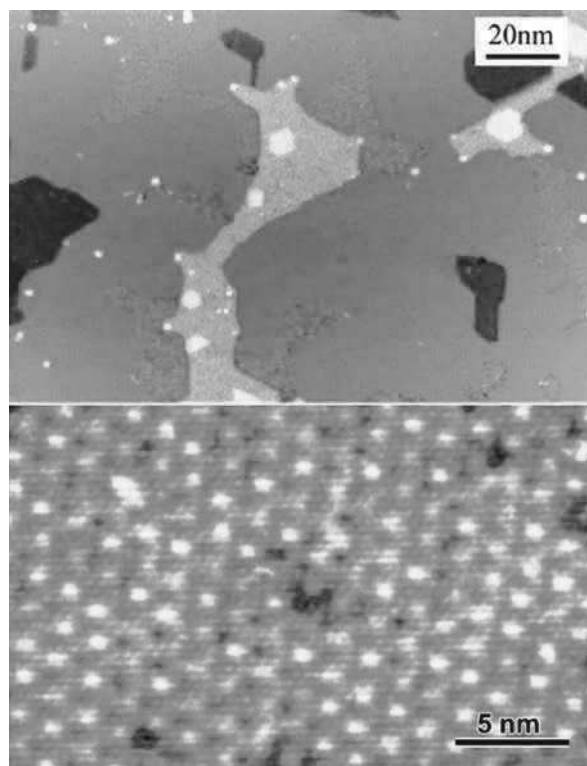
217 Among the other forms of synthesis, epitaxial graphene (EG) proved to be the  
218 most promising for metrological applications (Tzalenchuk et al. 2010). In their work,  
219 Tzalenchuk et al. fabricated EG devices and performed precision measurements,  
220 achieving quantization uncertainties of about 3  $\text{n}\Omega/\Omega$ . An example of their measure-  
221 ments is shown in Fig. 5, where (a) is a demonstration of how viable the graphene-  
222 based device was to be a suitable QHR standard. It was the start of a new chapter for  
223 standards, but additional work was required to exceed the stringent temperature  
224 requirement of 300 mK and low current capability of 12  $\mu\text{A}$ , relative to modern day  
225 capabilities (Tzalenchuk et al. 2010). EG graphene as QHR standards soon provided  
226 increased current capability and showed impressive plateau width for high and low  
227 magnetic field and higher temperatures. EG was also synthesized on SiC via CVD in  
228 2015, showing that graphene could provide standards-quality resistance at temper-  
229 atures up to 10 K (Lafont et al. 2015). This CVD method relied on the SiC substrate  
230 to provide a template for the growth of EG from a gas containing a hydrocarbon  
231 precursor.

### 232 **Establishing Graphene as a Global Resistance Standard**

233 EG has been used as part of the traceability chain of electrical resistance dissemina-  
234 tion in the United States since early 2017 (Janssen et al. 2011; Oe et al. 2019;  
235 Woszczyna et al. 2012; Satrapinski et al. 2013; Rigosi et al. 2019a). The preceding



**Fig. 4** Scanning tunneling microscopy images (taken at 0.8 V sample bias, 100 pA) show a single layer of epitaxially grown graphene on SiC(0001). The top and bottom panels show two different magnifications of a neighborhood of the grown crystal. (Reprinted from (De Heer et al. 2007))



**Fig. 5** The Hall resistance quantization accuracy was determined in these measurements. **(a)** The mean relative deviation of  $R_{xy}$  from  $R_K/2$  is shown at different currents (ppb, or  $n\Omega/\Omega$ ) on the right vertical axis. Recall that  $R_{xy}$  is nominally measuring the  $\nu = 2$  plateau of the QHE. The value of the deviation at the smallest current was measured at 4.2 K (blue squares), and all other measurements were performed at 300 mK (red squares). To achieve the highest accuracies, using an 11.6  $\mu\text{A}$  source–drain current (14 T, 300 mK), at least one of the measurements was performed over 11 h. The right vertical axis shows  $R_{xx}/R_K$ , which is represented as the black star along with its measurement uncertainty. **(b)** The Allan deviation of  $R_{xy}$  from  $R_K/2$  is plotted as a function of time (of the measurement). The square root dependence (as fit by the solid red curve) is indicative of white noise. (Reprinted by permission from Springer Nature Customer Service Centre GmbH: (Tzalenchuk et al. 2010))

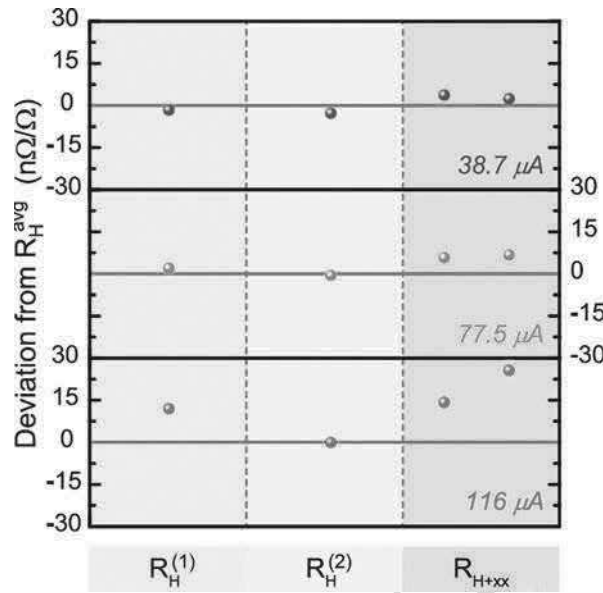
236 years from 2010 onward were dedicated to the study of basic fabrication processes  
237 and measurement techniques so that EG-based QHR devices could be accepted as  
238 the replacement for GaAs-based QHR devices. With optimized EG devices, perfor-  
239 mance far surpassed that of the best GaAs-based devices. A compilation of these  
240 efforts can be linked to multiple institutes (Lara-Avila et al. 2011; Rigosi et al. 2017,  
241 2018, 2019b; Riedl et al. 2010; Janssen et al. 2015; Kruskopf et al. 2016; He et al.  
242 2018). EG-based devices suitable for metrology required high-quality EG to the  
243 point of substantial scalability (centimeter-scale) as well as stabilization of electrical  
244 properties to have a long shelf life and end-user ease-of-use.

245 In one example of EG-based QHR development, implemented by two separate  
246 groups, devices had become compatible with a 5 T table-top cryocooler system  
247 (Rigosi et al. 2019a; Janssen et al. 2015). Janssen et al. first demonstrated this type of  
248 measurement with a table-top system in 2015, pushing the bounds of operability to  
249 lower fields and higher temperatures. The advantage of such a system also includes  
250 the removal of the need for liquid helium, enabling continuous, year-round operation  
251 of the QHR without the use of liquid cryogenes. The  $\nu = 2$  plateau in EG devices is  
252 the primary level used to disseminate the ohm, much like for GaAs-based QHRs. In  
253 fact, EG provides this plateau in a very robust way and for a large range of magnetic  
254 fields because of Fermi level pinning from the covalently bonded, insulating carbon  
255 layer directly beneath the conducting graphene layer (Lara-Avila et al. 2011).

256 For the 5 T table-top system at the National Institute of Standards and Technology  
257 (NIST), the EG QHR device plateau value was scaled to a 1 k $\Omega$  standard using a  
258 binary CCC and a DCC (Rigosi et al. 2019a). The uncertainties that were achieved  
259 with this equipment matched those obtained in GaAs-based QHR systems (i.e., on  
260 the unit order of n $\Omega/\Omega$ ). The results of some of these measurements are shown in  
261 Fig. 6 at three different currents. The limit of nearly 100  $\mu$ A gives EG-based QHRs  
262 the edge over GaAs, especially since these measurements were performed at approx-  
263 imately 3 K. Another example of graphene being established as the new QHR  
264 standard comes from Lafont et al., whose work hardened the global question of  
265 when graphene would surpass GaAs in various respects (Lafont et al. 2015). An  
266 example of this investigation is shown in Fig. 7, where the sample of choice was  
267 CVD-grown epitaxial graphene on SiC. Overall, with the success of the national  
268 institute's QHR efforts, the evidence for EG-based devices surpassing GaAs-based  
269 QHRs has been widely accepted.

## 270 Improvements in Measurement Infrastructure

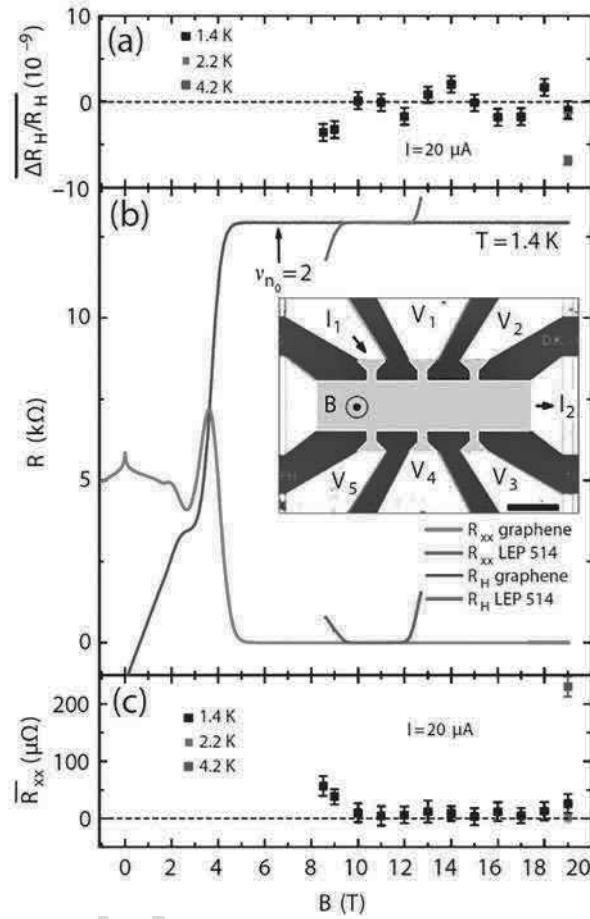
271 Given the establishment of better QHR devices for resistance standards, the  
272 corresponding equipment and infrastructure with which one can disseminate the  
273 ohm had to also improve or at least be shown to maintain its compatibility with  
274 EG-based QHRs. The measurement of the ratio between a QHR device and a  
275 standard resistor must achieve uncertainties that are comparable to or better than  
276 the stability of those resistors. This criterion would support the notion of reliable  
277 traceability in that system. Measurements with a longer integration time produce



**Fig. 6** Binary winding CCC measurements were performed with an EG-based QHR device in a cryogen-free table-top system at 5 T and 3 K. The CCC measurement data are displayed in three rows, with the upper, middle, and lower data corresponding to the source-drain currents of 38.7  $\mu\text{A}$ , 77.5  $\mu\text{A}$ , and 116  $\mu\text{A}$ , respectively. Each column shows a comparison between the resistance of the  $\nu = 2$  plateau and a 1 k $\Omega$  resistor, with the left two columns representing orthogonal contact pairs ( $R_H^{(1)}$  and  $R_H^{(2)}$ ). The third column represents the two diagonal pairs formed by the same contacts as the two orthogonal pairs. It is labelled as  $R_{H+xx}$  and indicates the impact of the residual longitudinal resistance. The type A measurement uncertainties are smaller than the data points, and the type B uncertainties are under 2  $\text{n}\Omega/\Omega$ . (© 2019 IEEE. Reprinted, with permission, from (Rigosi et al. 2019a))

278 better results because the ratios are well-maintained. The obvious benefits from  
 279 room-temperature bridge systems like the DCC include an ability to deliver mea-  
 280 surements to laboratories in both NMI and non-NMI settings with greater frequently  
 281 (year-round) due to their operation not requiring cryogenics (MacMartin and Kusters  
 282 1996). Additionally, both DCCs and CCCs have been improved so that they are  
 283 more user-friendly and automated, removing, at least in the case of the DCC, most of  
 284 the dependence on specialized knowledge that one normally expects for the more  
 285 complex cryogenic counterparts (Williams 2011; Drung et al. 2009). Some NMIs  
 286 have shown that the automated binary-ratio CCCs have type B uncertainties below  
 287 0.001  $\mu\Omega/\Omega$ , a useful feature when dealing with precise QHR comparisons (Sullivan  
 288 and Dziuba 1974; Grohmann et al. 1974; Williams et al. 2010). CCC scaling  
 289 methods can achieve resistance ratios of 4000 or more, enabling measurements for  
 290 sub-nanoampere current levels, whereas DCCs achieve similar current sensitivity  
 291 only with larger currents.

292 The DCC is a room-temperature current comparator, and this simplifies the  
 293 operation and cost compared to SQUID-based CCC systems. The work by



**Fig. 7** The magnetic field dependence for Hall resistance in CVD-grown epitaxial graphene is shown. (a) The Hall resistance ( $R_H$ ) deviation is measured on the  $\nu = 2$  plateau at 1.4 K (black), 2.2 K (magenta), and 4.2 K (violet). (b)  $R_{xx}$  and  $R_H$  were measured with a source-drain current of 20  $\mu\text{A}$ , with both types of voltages measured using the ( $V_1$ ,  $V_2$ ) and ( $V_2$ ,  $V_3$ ) contact pads, respectively. The magnetic field was energized to values between 1 T and 19 T for the graphene device (shown by the red and blue curves) and from 8 T to 13 T for the GaAs device (maroon and gray curves). The onset of the Landau level was calculated by using the carrier density at low magnetic fields, which is related to the slope of  $R_H$  near zero field. The inset shows an optical image of the device (scale bar is 100  $\mu\text{m}$ ). (c) Data for precision measurements of  $R_{xx}$  are shown at 1.4 K (black), 2.2 K (magenta), and 4.2 K (violet). The error bars represent combined standard uncertainties ( $1\sigma$ ). (Lafont et al. (2015) is an open-access article distributed under the terms of the Creative Commons CC BY license, which permits unrestricted use, distribution, and reproduction in any medium)

294 MacMartin and Kusters shows the development of a DCC for comparing four-  
 295 terminal resistances (MacMartin and Kusters 1996). It works by measuring a current  
 296 ratio, represented as a turns ratio, that is balanced by detecting magnetic hysteresis in  
 297 magnetic cores using a modulator. Manual dials allowed the ratio to be adjustable in

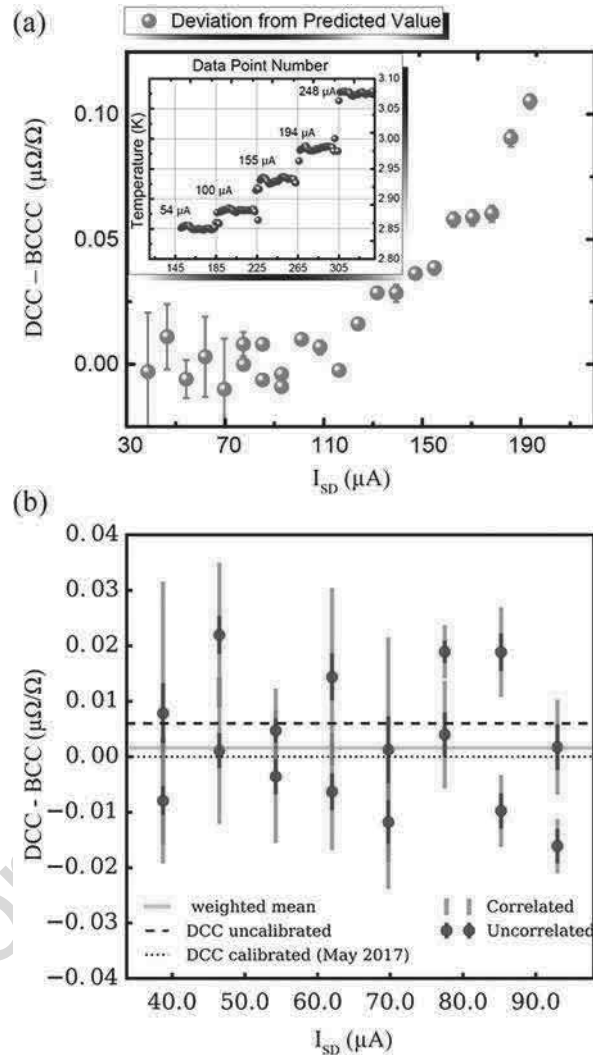
298 part-per-million steps. The two current sources in the DCC are isolated so that there  
299 is no current in the galvanometer circuit when fully balanced. Their DCC was able to  
300 measure and compare the ratio of two isolated direct currents and adjust the ratio to  
301 balance the galvanometer. A detailed description provided a discussion of its accu-  
302 racy limitations (MacMartin and Kusters 1996). In the optimum operating range, the  
303 authors achieved accuracies that were better than one part per million. The bridge  
304 was designed to accommodate the scaling of resistance standards from 100  $\Omega$  to a  
305 less than 1 m $\Omega$  and can be used for any ratio from 1 to 1000, thus permitting one to  
306 calibrate low value resistors and current shunts whose accuracies would be limited  
307 only by the level of noise and the stability of the resistor (MacMartin and Kusters  
308 1996). Modern DCC systems are fully automated to control current levels, ratios,  
309 and resistance values, and allow scaling of resistance standards from 100 k $\Omega$  to  
310 below 10  $\mu\Omega$ .

311 From the previously mentioned work at NIST (Rigosi et al. 2019a), the two  
312 bridges demonstrate the applicability of using a modern room-temperature DCC  
313 with an EG-based QHR device to obtain uncertainty near 0.01 m $\Omega/\Omega$ . As shown in  
314 Fig. 8a, the DCC measurements extend the range of the applied source-drain currents  
315 when scaled from the EG-based QHR device to a 1 k $\Omega$  resistor. The inset of Fig. 8a  
316 shows how sample heating from a high applied current affects the overall sample  
317 temperature. This information was relevant because high currents applied to  
318 EG-based QHR devices improves the resolution of the DCC measurements, but  
319 will degrade the accuracy of the QHE due to too high a temperature. Ultimately, the  
320 work found that table-top systems, in which the QHR is cooled indirectly by  
321 conduction and is in vacuum, may limit how much current can be applied (Rigosi  
322 et al. 2019a). Larger cryomechanical chillers are designed to immerse the device in a  
323 small volume of liquid helium and provide better temperature stabilization by  
324 contact with the liquid bath.

325 As of the present day, CCC bridges outperform DCCs in terms of achievable  
326 uncertainties. However, in order to more easily disseminate QHR technology glob-  
327 ally, room temperature DCCs are preferred in terms of ease-of-use and fewer  
328 resource needs as well as year-round operability. For this reason, a comparison  
329 between the two methods was examined and is shown in Fig. 8b, where the number  
330 of DCC data points averaged was varied inversely with the square of the applied  
331 voltage  $V \approx I_{SD} \times R_H$  to obtain a similar type A uncertainty for all values of the  
332 source-drain current, with measurement durations ranging from 110 min for the  
333 0.5 V measurements to 24 min for the 1.2 V measurements. Further, in Fig. 8b, the  
334 uncertainties indicated in blue were produced by the DCC software. The larger, red  
335 error bars are uncertainties that take into account known statistical correlations in the  
336 data (Zhang 2006). Potential noise from the cryogen-free mechanical refrigeration  
337 system may also interfere to some degree with the balancing algorithm. A similar  
338 issue exists for CCC systems, where the additional noise from vibration may  
339 increase noise and may cause the SQUID to lose the delicate balance required to  
340 maintain its set point through feedback.

341 Even though DCCs would make global dissemination easier for some research  
342 institutes and smaller NMIs, CCC technology is still important for international  
343 metrology at the highest levels. Williams et al. demonstrated a design for an

**Fig. 8** (a) Current dependence data of DCC ratios for a 1 k $\Omega$  resistor are shown in magenta, based on the same EG QHR device used with a binary winding CCC (BCC). The DCC results confirm that the QHR device remains quantized to within 0.01  $\mu\Omega/\Omega$  up to approximately 116  $\mu\text{A}$ . Data for higher source-drain currents shows the effect of heating of the sample caused by power dissipation, with temperature data for extended current ranges shown in the inset with blue data points. Some type A measurement uncertainties (in red) are smaller than the data points. (b) DCC data for the ratio of the QHR to 1 k $\Omega$  are shown for increasing source-drain currents from 38  $\mu\text{A}$  to 94  $\mu\text{A}$  and are normalized to the average results of BCC scaling (using 38.7  $\mu\text{A}$  and 77.5  $\mu\text{A}$ ). The red error bars show the expanded ( $k = 2$ ) with uncorrelated uncertainties whereas the blue error bars show the expanded ( $k = 2$ ) uncertainty reported by the measurement device. (© 2019 IEEE. Reprinted, with permission, from (Rigosi et al. 2019a))



344 automated CCC in order to perform routine NMI measurements (Williams et al.  
 345 2010). Their system uses a CCC in a low loss liquid helium storage vessel and may  
 346 be continuously operated with isolated supplies coming from the mains power. All  
 347 parameters were shown to be digitally controlled, and the noise sources present in  
 348 the system were analyzed using the standard Allan deviation, leading to the conclusion  
 349 that one may eliminate non-white noise sources simply by choosing the  
 350 appropriate current reversal rate. New generations of CCC systems with integrated  
 351 fast ramping current sources, nano-voltmeter, and a compensation network for  
 352 improved bridge balancing have become widely used at worldwide NMIs (Drung  
 353 et al. 2009).



354 As progress continues, NMIs have both anticipated and in many cases achieved  
355 these goals for EG-based QHR devices. Lastly, to begin expanding on the function-  
356 ality of EG-based devices, it would need to be shown that precise resistance scaling  
357 could be done to reference resistors from the QHR by using voltages larger than  
358 those available in standard DCCs and CCCs. These efforts are underway and hope to  
359 eventually accelerate dissemination efforts.

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## 360 **Expanding the Use of the Quantum Hall Effect in Graphene**

### 361 **Assembly of p-n Junctions in Graphene-Based Devices**

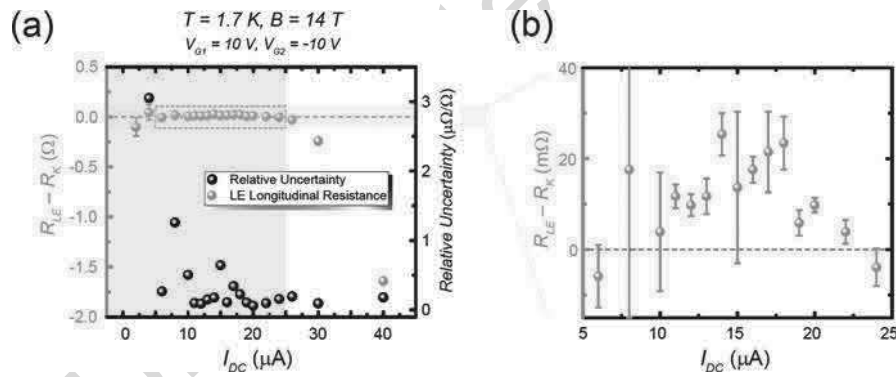
362 With EG-based QHR devices established as national standards at several NMIs, as  
363 well as the metrology community in agreement that comparisons against GaAs-  
364 based QHR devices had been accomplished, the next steps became clearer  
365 concerning how the EG-based QHR could be further developed. Unlike the QHR  
366 in GaAs, only the  $\nu = 2$  plateau is well quantized, and although other Landau levels  
367 exist in graphene, they simply do not offer the same level of precision as the  $\nu = 2$   
368 plateau (Zhang et al. 2005; Hu et al. 2021). Since the early 1990s, it has been of  
369 interest that QHR devices have a means of interconnecting several single Hall bar  
370 elements without loss of precision, and this has since been of great research interest.

371 As discussed earlier, this work allowed QHR devices to output more than the single  
372 value at the  $\nu = 2$  plateau (about 12.9 k $\Omega$ ) through arrays of devices, using what are  
373 described as multi-series interconnections (Delahaye 1993). With graphene, which  
374 supports both electron conduction and hole conduction (with positive carrier charge)  
375 the first natural question is whether one may use the plateau at  $\nu = -2$ , in addition to  
376 the plateau at  $\nu = 2$ . This array would avoid the need for manufactured intercon-  
377 nections entirely, using an interface of electronic states internal to the 2D conductor.

378 This alternative for outputting new quantized values utilizes *p-n* junctions (*pnJs*) to  
379 provide useful and controllable values of resistance quantization (Hu et al. 2018a, b;  
380 Woszczyna et al. 2011; Rigosi et al. 2019c; Momtaz et al. 2020). Woszczyna et al.  
381 approached this issue a decade ago (Woszczyna et al. 2011), noting that since metallic  
382 leads had to cross paths in traditional GaAs-based devices, typical fabrication methods  
383 would be overly complicated, having to include some form of multilayer interconnect  
384 technology. Any leakage between leads would likely generate an additional Hall  
385 voltage, thus becoming a detriment to the achievable uncertainty. Graphene is more  
386 accessible for the fabrication of small structures than the GaAs heterostructure inter-  
387 face, where contacts must be alloyed through the insulating surface layer. Charge  
388 carrier control by gating offered the opportunity to combine two regions of opposite  
389 charge carrier polarity. Rather than requiring interconnections, such a device only  
390 needs a set of uniform top gates to modulate regions between the  $\nu = -2$  and  $\nu = 2$   
391 plateaus. This work demonstrated that *pnJs* were possible and worth exploring as a  
392 viable extension for QHR standards.

393 The fabrication of *pnJ* devices larger than the order 100  $\mu\text{m}$  is presently limited by  
394 the difficulty of producing of high-quality, exfoliated single-crystal hexagonal boron  
395 nitrate (*h*-BN) as an insulating material for top gating. As demonstrated by Hu et al.,

396 numerous pnJ's can be fabricated in a single device of size  $100\ \mu\text{m}$  or less, rendering  
 397 it possible to implement reliable top gates for adjusting the carrier density in gated  
 398 EG-based devices (Hu et al. 2018a). The underlying physics of these *pnJ*s makes it  
 399 possible to construct devices that can access quantized resistance values that are  
 400 fractional or integer multiples of  $R_K$ . Hu et al. made an assessment for one such *pnJ*  
 401 device at the  $\nu = -2$  and  $\nu = 2$  plateaus (summing to about  $25.8\ \text{k}\Omega$ ), with data  
 402 shown in Fig. 9. A DCC was used to provide turn-key resistance traceability and  
 403 compare against a  $10\ \text{k}\Omega$  standard resistor (see Fig. 9a). The measurement time for  
 404 each data point with the DCC was 15 min, with an orange shaded region representing  
 405 Fig. 9b, which clarifies the deviation of the DCC measurements with respect to zero.  
 406 In Fig. 9a, the right axis is represented by black points and gives the relative  
 407 uncertainty of each measurement as a function of source-drain current. For this  
 408 *pnJ* device, a precision of about  $2 \times 10^{-7}$  was achieved as shown in Fig. 9b. Although  
 409 this may be one or two orders of magnitude below what is possible for a conven-  
 410 tional Hall bar device, one must recall that, based on this work, a programmable  
 411 resistance standard may be built using the demonstrated techniques. Such flexibility  
 412 and expansion of accessible parameter space could justify its further technical  
 413 exploration within resistance metrology.  
 414 These types of devices are not as well-studied as other conventionally prepared  
 415 devices, but given their interesting and rather unique properties, *pnJ* devices could



**Fig. 9** (a) The lower edge (LE) of the device in Hu et al. was compared against a  $10\ \text{k}\Omega$  standard resistor with a DCC to give an assessment of the quality of quantization exhibited by the device. The resistor was selected based on its traceability to a quantum resistance standard at the National Institute of Standards and Technology. The turquoise points show the DCC measurements as deviations from  $R_K$  on the left axis and the relative uncertainties of those deviations with DC current. The relative uncertainties improve with increasing current, but the device loses its optimal quantization after the critical current of  $24\ \mu\text{A}$ . The shaded green area indicates the well-quantized region. (b) The beige shaded area in (a) is magnified to show the deviations' error bars as well as the reference to zero deviation, marked as an orange dashed line. The error bars represent a  $1\sigma$  deviation from the mean, where each data point represents an average of a set of data taken at each value of current. (Hu et al. (2018a) is an open access article distributed under the terms of the Creative Commons CC BY license, which permits unrestricted use, distribution, and reproduction in any medium)

416 offer a second, more fundamental path to avoid any resistance from interconnecting  
417 metallic contacts and multiple device connections. This possibility is illustrated in a  
418 recent experiment by Momtaz et al. and demonstrates how a programmable quantum  
419 Hall circuit could implement an iterative voltage bisection scheme, thus permitting  
420 the user to access any binary fraction of the  $\nu = 2$  plateau resistance (Momtaz et al.  
421 2020). Their proposed circuit designs offer potential advantages for resistance  
422 metrology, as summarized here: first, their circuit contains no internal Ohmic  
423 contacts, a recurring problem in interconnected QHR circuits. Second, there is a  
424 logarithmic scaling of the complexity of the design as a function of the required  
425 fractional resolution. This scaling feature is a major advantage compared with a  
426 standard QHARS device. The latter might use hundreds of distinct multi-contact  
427 Hall bars, whereas a bisection circuit can output a similar number of values while  
428 only needing a small number of elements. The approach is thought to match, or  
429 become comparable to, the present limits of QHR standards.

430 The design does have some limitations, as pointed out by Momtaz et al. They  
431 noted that, even though the last bisection stages of the device were controlling a finer  
432 portion of the output value, each stage still relied on QHE states equilibrating across  
433 a junction barrier, emphasizing the importance of the quality of the junction itself.  
434 Their preliminary numerical estimates suggest that imperfections in the device  
435 would be partially fixable since any absolute errors caused by imperfect mixing  
436 would not be amplified through the remaining sections of the device. Nonetheless,  
437 this design warrants further study as one way to expand on available quantized  
438 resistance outputs.

### 439 **Using Arrays to Expand the Parameter Space**

440 Recent developments have utilized superconducting materials like NbN and NbTiN  
441 to create interconnections compatible with EG-based QHR devices (Kruskopf et al.  
442 2019a, b; He et al. 2021). These metals have high critical temperature ( $\approx 10$  K) and  
443 critical field ( $\approx 20$  T) so that they may be applied to QHR devices during measure-  
444 ment, as shown by Kruskopf et al. (2019b). They argue that array technology based  
445 on superconducting metals is preferred and can eliminate accumulated resistance and  
446 voltage errors at contacts and interconnections. They demonstrated that the applica-  
447 tion of NbTiN, along with superconducting split contacts, enabled both four-terminal  
448 and two-terminal precision measurements without the need for insulated crossovers.  
449 The split contacts are inspired by the multiple series approach described by Delahaye  
450 (1993), with reduced separation between the interconnections. Since the resulting  
451 contact resistances become much smaller than  $R_K$ , it becomes straightforward to  
452 fabricate series and parallel connections as fundamental device elements. The limits  
453 of this technology have not yet been determined, nonetheless, the merits of this  
454 technique seem to point to such structures as the next generation of QHR devices.

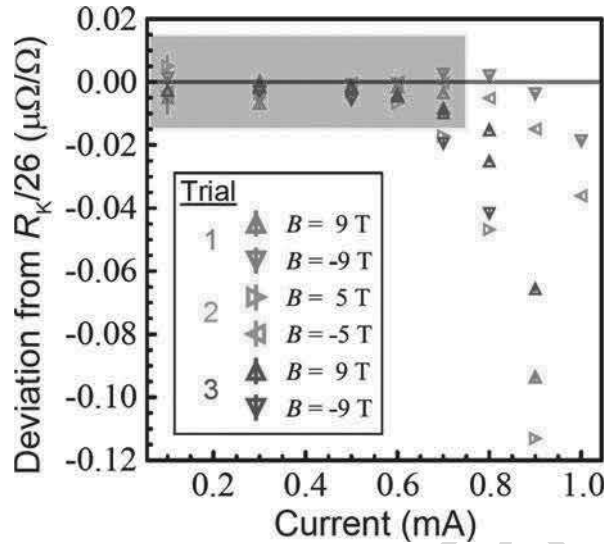
455 Another example of array technology that expands on the parameter space comes  
456 from Park et al. (2020), where they successfully construct 10 single Hall bars in  
457 series with EG on SiC. They operated this device at the  $\nu = 2$  plateau near 129 k $\Omega$

458 with precision measurements made using a CCC. While measuring the device at a  
459 magnetic field of 6 T and a temperature of 4 K, they were able to achieve a relative  
460 uncertainty of approximately  $4 \times 10^{-8}$ , approaching the state-of-the-art for this  
461 resistance level. Despite only being able to inject a low double-digit electrical current  
462 (in  $\mu\text{A}$ ), their efforts added support to the notion of expanding QHR values with  
463 QHARS devices.

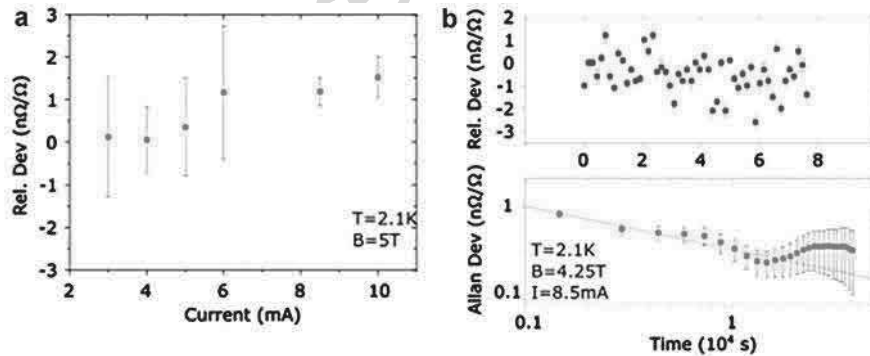
464 One difficulty that could arise from making these arrays, especially as they  
465 increase in lateral size, is how to make their carrier densities uniform. For that,  
466 there are two prime examples of accomplishing this task, with both methods being  
467 user-friendly and attaining a long shelf life for the device. The first method involves  
468 functionalizing the EG surface with  $\text{Cr}(\text{CO})_3$  (Rigosi et al. 2019b), and what this  
469 process enables the user to do is apply heat for a specified time to obtain a predictable  
470 carrier density. The advantage is that this process is reversible and may be cycled  
471 without damaging the device. One of the features of this method is that storing the  
472 device in air for long periods of time simply resets the Fermi level to an energy close  
473 to the Dirac point. The same anneal may be applied to reacquire the value of the  
474 carrier density. Once in an inert environment or at colder temperatures, the carrier  
475 density of the device remains stable. The second method involves a polymer-assisted  
476 doping process (He et al. 2018), which allows the user to adjust the carrier density by  
477 also using an anneal. This method retains some reversibility as long as the polymer  
478 will retain its matrix. Both methods are highly scalable and give extended shelf life  
479 to EG-based standards.

480 With the ability to make very large QHARS devices having controllable and  
481 uniform carrier densities, researchers were able to construct a  $1 \text{ k}\Omega$  array based on  
482 13 single Hall bar elements in parallel (Hu et al. 2021). A CCC was used to measure  
483 two 13-element arrays. At 1.6 K, the array devices achieved useful quantization  
484 above 5 T. One such array measurement is shown in Fig. 10. In this case, the DCC  
485 measurements verified that, in the high-field limit, the resistance for both  $B$ -field  
486 directions approached the value  $R_K/26$  (about  $992.8 \Omega$ ) to better than one part in  $10^8$   
487 for currents up to  $700 \mu\text{A}$ . As is typical, the CCC ratio uncertainty was below one  
488 part in  $10^9$ , and most of the uncertainty had originated from the  $100 \Omega$  artifact  
489 resistance standards (Fig. 11).

490 Recent work by He et al. shows quantum Hall measurements performed on a  
491 large QHARS device containing 236 individual EG Hall bars (He et al. 2021). Given  
492 the difficulty of verifying the longitudinal resistance as zero for every element, they  
493 utilized a direct comparison between two similar EG-based QHARS devices to  
494 verify the accuracy of quantization. The design of this array is such that two  
495 subarrays with 118 parallel elements are connected in series, having a nominal  
496 resistance of  $h/236e^2$  (about  $109.4 \Omega$ ) at the  $\nu = 2$  plateau. The Hall bars were  
497 designed to be circular in order to both have a symmetrical design and to be able to fit  
498 many devices into a small area (He et al. 2021). The contact pads and interconnec-  
499 tions were fabricated from NbN and support currents on the order of 10 mA at 2 K  
500 and 5 T. Additionally, a split contact design was implemented to minimize the  
501 contact resistance, much like other previously reported work (Kruskopf et al.  
502 2019a, b). The two QHARS devices were compared using high precision



**Fig. 10** The  $\nu = 2$  plateau was measured at selected values of the magnetic field ( $B$ ) for device 1 at 1.6 K in a conventional cryostat using a room-temperature DCC. DCC measurements verify that, in the high-field limit, the resistance for both  $B$ -field directions approaches the value  $R_K/26$  (about  $992.8 \Omega$ ) to better than one part in  $10^8$  for currents up to  $700 \mu\text{A}$ , confirming that this array device utilizes highly homogeneous graphene. All expanded uncertainty values given here are for a  $2\sigma$  confidence interval. (Hu et al. (2021) is an open access article distributed under the terms of the Creative Commons CC BY license, which permits unrestricted use, distribution, and reproduction in any medium)



**Fig. 11** High bias current measurements on arrays. (a) CCC measurements are shown of a direct comparison between subarrays to show that no significant deviation occurs until 8.5 mA. The data consist of the mean of 5–10 CCC readings, each of which is 20 min long. The top graph shows the relative deviation, with error bars of one standard deviation. The bottom graph shows the corresponding Allan deviation. The standard error is limited to  $0.25 \text{ n}\Omega/\Omega$ . (He et al. (2021) is an open access article distributed under the terms of the Creative Commons CC BY license, which permits unrestricted use, distribution, and reproduction in any medium)

503 measurements, showing no significant deviation of their output resistance within  
504  $0.2 \text{ n}\Omega/\Omega$ . Within the next few years, given the increasing complexity of EG-based  
505 QHARS devices, even larger and more versatile arrays are expected to make  
506 available an abundance of new quantized resistance values.

## 507 **From DC to AC to the Quantum Ampere**

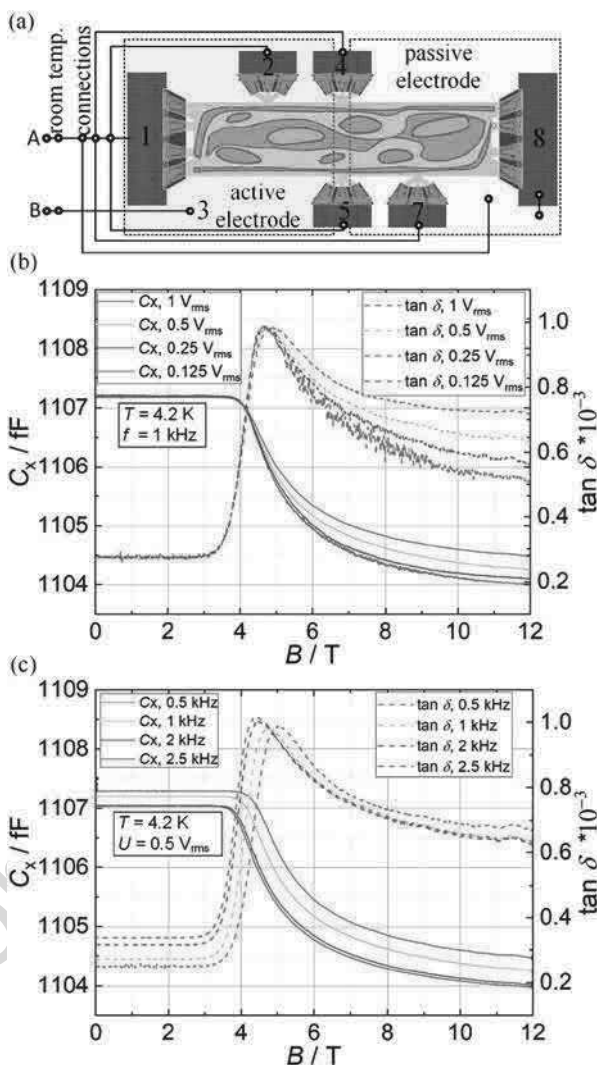
508 As the *quantum* SI continues to expand in its applications, new research directions  
509 are plentiful and of interest to the electrical metrology community. The QHE will  
510 continue to be our foundation for disseminating the ohm in the DC realm. The vast  
511 improvements in EG-based QHR technology are beginning to inspire efforts to  
512 develop more sophisticated devices suitable for AC resistance standards. This  
513 subfield of electrical metrology focuses on the calibration of impedance and is  
514 conventionally obtained from systems like a calculable capacitor (Thompson and  
515 Lampard 1956; Clothier 1965; Cutkosky 1974). Such a system has allowed for the  
516 calibration of capacitors, inductors, or AC resistors, which is essentially a measure-  
517 ment of complex ratios of impedance, where the signal phase depends on the type of  
518 standard. Historically, the design and operation of this kind of system have been  
519 challenging because of unavoidable fringe electric fields, imperfections in capacitor  
520 electrode construction, and a long chain of required bridges and standards.

521 The next step for improving AC standards may be to introduce EG-based QHR  
522 devices, as Kruskopf et al. have done recently (Kruskopf et al. 2021). They used a  
523 conventional EG-based device to analyze the frequency dependence of losses and to  
524 determine the characteristic internal capacitances. The environment of the device  
525 included a double shield used as an active electrode, to compensate for capacitive  
526 effects, as shown in Fig. 12a. Figure 12b displays the set of magnetocapacitance  
527 measurements corresponding to a configuration of the capacitance ( $C_x$ ) between the  
528 active electrode (left side of (a)) and the EG Hall bar between points A and B in  
529 Fig. 12a.  $C_x$  was compared with a variable precision reference capacitor using a  
530 simple configuration used for other traditional measurements (Kruskopf et al. 2021).  
531 Figure 12a shows the passive electrode on right side, shorted to the EG contact, and  
532 therefore not contributing to the measurement of  $C_x$ .

533 The AC QHR may directly access the units of capacitance and inductance with  
534 high precision (Kruskopf et al. 2021; Lüönd et al. 2017). Kruskopf et al. show the  
535 voltage and frequency dependencies of the magnetocapacitance in Fig. 12b, c,  
536 respectively, along with the associated dissipation factor for an example device.  
537 By appropriately modeling the compressible and incompressible states, the observed  
538 dissipation factors may be explained rather well. At low magnetic field values, the  
539 2D electron system in the EG is not quantized and is thus accurately representable as  
540 a semi-metal with dominant compressible states. However, when the magnetic field  
541 is increased,  $C_x$  starts to decrease around 4 T and does so by nearly 3 fF in both cases  
542 as 12 T is approached. This phenomenon may be due to the increase in incompress-  
543 ible regions that form, which are themselves transparent to electric fields. Further-  
544 more, the dissipation factor is observed to first increase, peaking during the transition



**Fig. 12** Magnetocapacitance measurement data of an example device are shown (taken at 4.2 K). (a) An illustration captures the various elements of the used magnetocapacitance measurement configuration. As one electrode gets shorted to the labeled passive electrode (pin 8), the other electrode is then used to characterize  $C$  and  $\tan(\delta)$ . Compressible and incompressible states of the 2D electron system are represented as different colors within the EG Hall bar. (b) The capacitance is plotted as a function of magnetic field for a set of different voltages. (c) A similar plot to (b) is shown for a set of different frequencies. The dissipation factor ( $\tan(\delta)$ ) is also plotted representing the losses between the active electrode and the EG Hall bar device. (Kruskopf et al. (2021) is an open access article distributed under the terms of the Creative Commons CC BY license, which permits unrestricted use, distribution, and reproduction in any medium)



545 region as the resistance plateau in EG forms. As the quantization accuracy improves  
 546 at higher magnetic fields, the observed dissipative losses decrease again to about  $\tan$   
 547  $(\delta) = 0.0003$ . Overall, these are but a few magnetocapacitance measurements that  
 548 demonstrate the viability of efforts to better understand the physical phenomena  
 549 driving the observations made in the QHE regime while under AC conditions. This  
 550 pursuit of AC QHR standards aims to advance how units such as the farad and henry  
 551 are realized by using fundamental constants instead of dimensional measurements.

552 In addition to expanding the influence of the QHE to AC electrical metrology, one  
 553 may also expand into the realms of electrical current and mass metrology by utilizing

554 EG-based QHARS devices. The realization of the quantum ampere lacks accurate  
 555 traceability to within  $10^{-8}$  despite the various efforts that exist for developing a  
 556 current source using single-electron tunneling devices (Giblin et al. 2012; Pekola  
 557 et al. 2013; Koppinen et al. 2012). The alternative route one may take to realizing the  
 558 quantum ampere is by building a circuit that effectively combines the QHE and a  
 559 programmable Josephson junction voltage standard. This combination has been  
 560 recently assembled to attain a programmable quantum current generator, which  
 561 may disseminate the ampere at the milliamperage range and above (Brun-Picard  
 562 et al. 2016). The work reported by Brun-Picard et al. demonstrates this construction  
 563 with a superconducting cryogenic amplifier and to measurement uncertainties of  
 564  $10^{-8}$ . Their quantum current source, which is housed as two separate cryogenic  
 565 systems, can deliver accurate currents down to the microampere range. Considering  
 566 the orders of magnitude involved, this work renders the programmable quantum  
 567 current generator a pronounced supplement to electron-pumping mechanisms.

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## 568 Future Improvements and the Quantum Anomalous Hall Effect

### 569 Limitations to the Modern QHR Technology

570 In order to make an accurate assessment of future needs for quantum metrological  
 571 applications, it would benefit us to know the limits of the current technology, at least  
 572 to some extent. For instance, it is not known with substantial certainty how high a  
 573 current could be applied to a single EG Hall bar, or the upper bound on operational  
 574 temperature for EG-based devices.

575 There is much research to be conducted on newer technologies that build on the  
 576 single Hall bar design despite the noted benefits from their development. For  
 577 instance, the  $pnJ$  devices have conceptual access to different fractional or integer  
 578 multiples of  $R_H$  (or  $R_K/2$ ) as possible resistances, especially if source and drain  
 579 currents are allowed for more than two total terminals. If one defines  $q$  as a  
 580 coefficient of  $R_H$ , then the following relation may be used (Rigosi et al. 2020):

$$q_{M-1}(n_{M-1}) = \frac{q_{M-2}(n_{M-1} + 1)}{n_{M-1} + \frac{q_{M-2}}{q_{M-1}^{(0)}}} \quad (1)$$

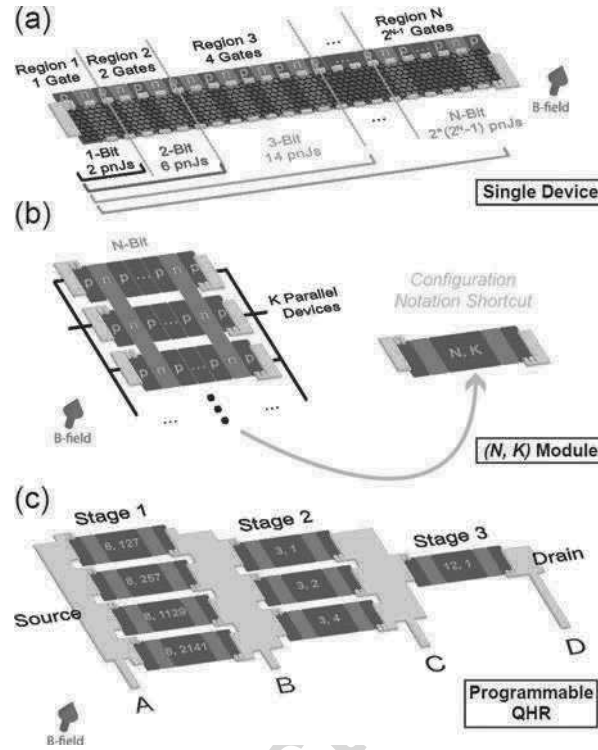
581 In Eq. (1),  $M$  is the number of terminals in the  $pnJ$  device,  $n$  is the number of  
 582 junctions between the outermost terminal and its nearest neighbor, and  $q_{M-1}^{(0)}$  refers to  
 583 a default value the device outputs when the configuration in question is modified  
 584 such that its outermost terminal moves to share the same region as its nearest  
 585 neighbor (meaning that one of the two outermost regions containing any source or  
 586 drain terminals has both a source and a drain connected to it) (Rigosi et al. 2020).  
 587 The key takeaway with this algorithm (Eq. 1) is that an incredibly vast set of  
 588 available resistances becomes hypothetically possible by simple reverse engineering.

589 The algorithm assumes that the Hall bar is of conventional linearity. That is, each  
590  $p$  region is adjacent to two other  $n$  regions unless it is an endpoint. The same would  
591 hold true when  $p$  and  $n$  are swapped. The equation breaks down when the  $pnJ$  device  
592 geometry changes to that of a checkerboard grid or Corbino-type geometry. In all of  
593 these cases, the available resistances in this parameter space are vastly abundant and  
594 will obviously not be a limiting factor for this species of device. Instead, limitations  
595 may stem from imperfections in the device fabrication, an almost inevitable mani-  
596 festation as the device complexity increases (Rigosi et al. 2019c).

597 In the limit of the purely hypothetical, should the resistance metrology commu-  
598 nity wish to scale to decade values only, as per the existing infrastructure, then a  
599 programmable resistance standard may be able to provide many decades of quan-  
600 tized resistance output by following the designs proposed by Hu et al. (2018a). The  
601 proposed programmable QHR device is illustrated in Fig. 13, with each subfigure  
602 defining a small component of a total device. When programmed in a particular way,  
603 this single device can output all decades between  $100\ \Omega$  and  $100\ M\Omega$ , as summarized  
604 by Table 1 (where voltage probes are labeled in reference to Fig. 13c).

605 With all  $pnJ$  devices, better gating techniques are warranted. In the case of top  
606 gating, which is the basis for forming the device measured by Hu et al. (2018a),  
607 fabrication is limited by the size of the exfoliated  $h$ -BN flake typically used as a high-  
608 quality dielectric spacer. For bottom gating of EG on SiC, as seen with ion implanta-  
609 tion (Waldmann et al. 2011), there has not yet been a demonstration of  
610 metrologically viable devices, though there may still be potential for perfecting  
611 this technique. Since gating is likely to be the largest limiting factor for  $pnJs$ , one  
612 must instead turn to array technology. Although QHARS devices can theoretically  
613 replicate  $pnJs$ , the necessity of an interconnection will ultimately result in a smaller  
614 available parameter space. Nonetheless, the output quantized resistance values  
615 offered by this technology may still be sufficiently plentiful for future applications  
616 in electrical metrology.

617 When it comes to arrays, there are several types that can take shape for a potential  
618 QHR device. There are the conventional parallel or series devices, which are the  
619 subject of recent works (Hu et al. 2021; Kruskopf et al. 2019a, b; He et al. 2021; Park  
620 et al. 2020). As one departs from this simpler design, the number of potential  
621 quantized resistances that become available rapidly increases. Designs with varying  
622 topological genera, as shown in Fig. 14, along with the predictive power of simu-  
623 lations like LTspice, Kwant, or traditional tight-binding Hamiltonians, allows the  
624 designer to customize devices accordingly. Depending on the genus and final layout,  
625 QHARS devices can still be metrologically verified by means of measuring a  
626 specific configuration and its mirror symmetric counterparts. In that sense, future  
627 QHARS devices whose longitudinal resistances cannot be checked must either be  
628 compared with a duplicate of itself, or must have appropriate symmetries such that a  
629 same-device comparison can be made. For instance, a square array could be the  
630 subject of a two-terminal measurement using same-sided corners. This configuration  
631 would have a four-fold symmetry which can be measured and compared to verify



**Fig. 13** The proposed device illustrated represents a programmable QHR device for scalable standards. (a) An  $N$ -bit device is illustrated showing how each region is defined and the maximum number of  $pnJs$  that can be used. (b) This device, when connected in parallel with  $K$  copies of itself, becomes the foundation of the  $(N, K)$  module. Each region has a set of gates that extend to all  $K$  parallel branches. (c) The proposed device is illustrated and composed of eight  $(N, K)$  modules, four of which are in parallel in stage 1, three of which are parallel in stage 2, and a single module in stage 3. All three stages are connected in series and all connections and contacts are proposed to be superconducting metal to eliminate the contact voltage differences to the greatest possible extent. The modules in stage 1 are 8-bit devices with more than 100 parallel copies per module, whereas the modules in stage 2 are 3-bit devices with four or fewer parallel copies per module. Stage 3 is a single 12-bit device with no additional parallel branches. These numbers for  $(N, K)$  are required should one wish to reproduce the values in Table 1. (Hu et al. (2018a) is an open access article distributed under the terms of the Creative Commons CC BY license, which permits unrestricted use, distribution, and reproduction in any medium)

632 device functionality. All types of arrays would be thus limited by the EG growth  
 633 area, which at present has been optimized by the use of a polymer-assisted sublima-  
 634 tion growth technique (Kruskopf et al. 2016). The total growth area may be the most  
 635 demanding limiting factor for this species of device. Nonetheless, one can hope that  
 636 the latter technique, and any similar technique to be developed, will enable homo-  
 637 geneous growth on the wafer scale such that the whole EG area retains metrological  
 638 quality.

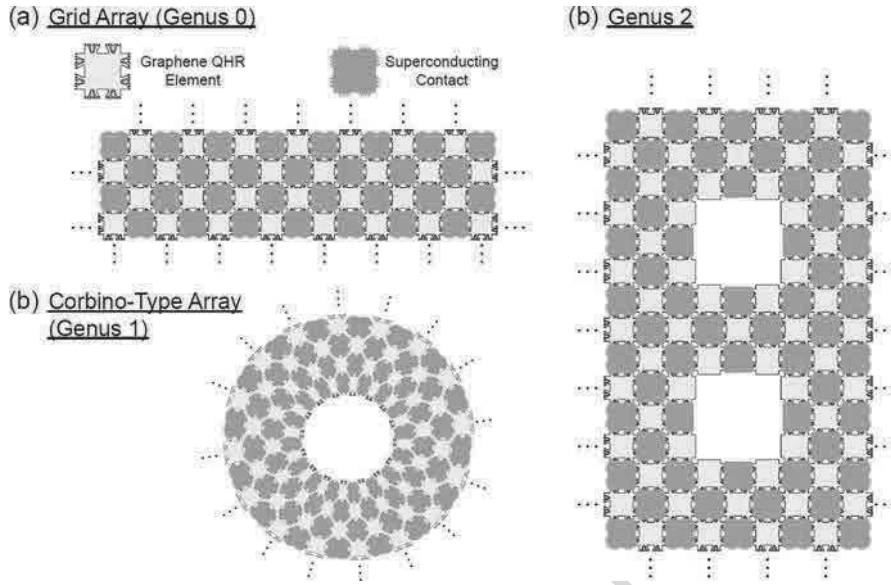
t.1 **Table 1** This shows all possible resistance decades achievable with the proposed programmable QHR device in Fig. 13

	Resistance	Stage 1	Stage 2	Stage 3	Voltage probes used	Deviation from decade value
t.2	100 $\Omega$	00010010 00011001 00001001 00010001	None	None	<i>A, B</i>	0.714 $\mu\Omega/\Omega$
t.3	1 k $\Omega$	10001001 10001011 10000111 10010001	None	None	<i>A, B</i>	0.108 $\mu\Omega/\Omega$
t.4	10 k $\Omega$	00110001 00100111 00110011 00111100	011 010 010	None	<i>A, C</i>	14.8 n $\Omega/\Omega$
t.5	100 k $\Omega$	00111101 00111101 00111100 00111110	010 010 010	00000000011	<i>A, D</i>	0.043 n $\Omega/\Omega$
t.6	1 M $\Omega$	00101011 00100001 00110101 00110000	010 001 001	000000100110	<i>A, D</i>	0.0243 n $\Omega/\Omega$
t.7	10 M $\Omega$	01011110 01011001 01010011 01001100	110 101 110	000110000010	<i>A, D</i>	0.346 p $\Omega/\Omega$
t.8	100 M $\Omega$	01110111 10001001 01101101 01100111	100 011 011	111100100001	<i>A, D</i>	1.21 n $\Omega/\Omega$

t.9 The values listed in this table are described in more detail in Hu et al. (2018a) and can achieve values of seven decades of resistance. Each module in each stage is assigned a binary string. As long as the exact configuration is used, the measured voltage between the two probes will measure a near-exact decade value, to within a deviation defined in the rightmost column. Hu et al. (2018a) is an open access article distributed under the terms of the Creative Commons CC BY license, which permits unrestricted use, distribution, and reproduction in any medium

### 639 The Quantum Anomalous Hall Effect

640 Regardless of EG device size, the magnetic field requirement will always be a limit.  
 641 This is inherently tied to the band structure of graphene. In addition to this limitation,  
 642 there are at least two others that prevent SI-traceable quantum electrical standards  
 643 beyond the ohm from being user-friendly and more widely disseminated, which at  
 644 present, confines their global accessibility to mostly NMIs. These other limitations  
 645 include the sub-nA currents obtained from single electron transistors (in the case of  
 646 the quantum ampere) and the Josephson voltage standard's aversion to magnetism,  
 647 complicating the use in a single cryostat with a QHR device to create a compact



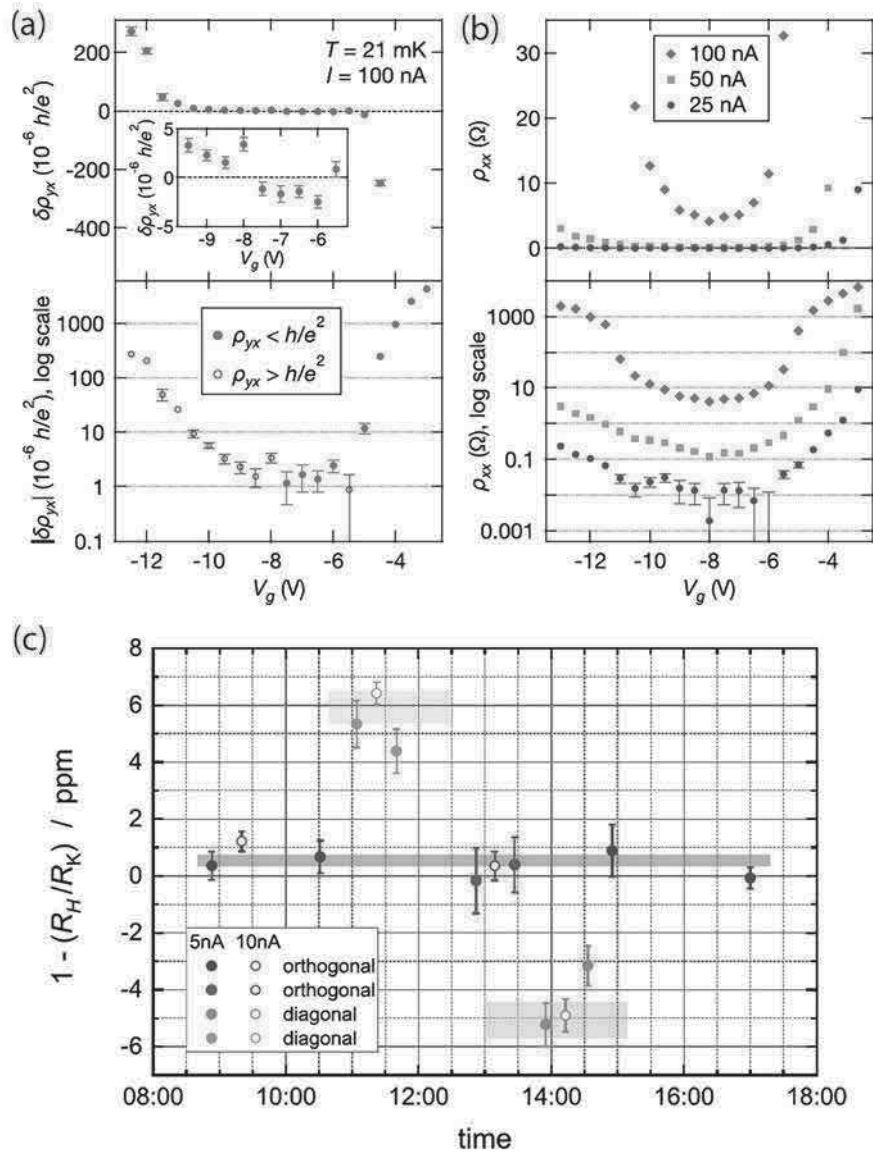
**Fig. 14** Hypothetical array designs of varying topological genera. Determining the predicted value of output quantized resistance between any pair of contacts can be done with various modeling techniques done for similar systems. (a) The use of superconducting contacts enables the design of larger and more complex arrays, provided the EG QHR elements are small enough. For genus 0, grid arrays can take on user-defined dimensions. (b) Corbino-type geometries could also be implemented, and these are just examples of genus 1 topologies. (c) A final example of array type comes from those that have a genus 2 topology. Even more customized designs are possible and not well-explored

648 current standard. Ongoing research on magnetic topological materials has the poten-  
 649 tial to avoid compatibility problems.

650 The physical phenomenon underpinning this research is the quantum anomalous  
 651 Hall effect (QAHE). This effect yields a quantized conductance in magnetically  
 652 ordered materials at zero applied magnetic field. Certain types of material display a  
 653 quantized resistance plateau at zero-field suitable for metrology measurements, as  
 654 has been shown in some recent work (Fox et al. 2018; Götz et al. 2018). The QAHE  
 655 is a manifestation of a material's topologically nontrivial electronic structure. The  
 656 QAHE, along with the Josephson effect and QHE, is a rare example of a macro-  
 657 scopic quantum phenomenon. There are several types of materials that exhibit the  
 658 QAHE, with many being classified within the following categories: magnetically  
 659 doped topological insulators (TIs), intrinsic magnetic TIs, and twisted van der Waals  
 660 layered systems.

661 Fox et al. explored the potential of the QAHE in a magnetic TI thin film for  
 662 metrological applications. Using a CCC system, they measured the quantization of  
 663 the Hall resistance to within one part per million and, at lower current bias, measured  
 664 the longitudinal resistivity under 10 mΩ at zero magnetic field (Fox et al. 2018). An  
 665 example of the data they acquired is in Fig. 15a, b. When the current density was





**Fig. 15** (a) CCC data are shown for measurements of  $\rho_{yx}$  in an example device using a 100 nA current at 21 mK. The plateau in the upper panel shows the deviation from  $R_K$  for a range of gate voltages. The inset shows a magnified view of the Hall resistance deviations in the center of the plateau ( $\nu = 1$ ). The bottom panel shows the logarithmic behavior of the deviations as one departs from the optimal gate voltage. (b)  $\rho_{xx}$  of the same device was measured as a function of gate voltage for three different bias currents. The data show strong current and gate voltage dependence, as displayed on a linear and log scale in the top and bottom panels, respectively. At 25 nA, with the gate voltage near the center of the plateau, the resistivity nearly vanishes and the measurements approach the noise floor. All error bars show the standard uncertainty and are omitted when they are

666 increased past a critical value, a breakdown of the quantized state was induced, and  
667 this effect was attributed to electron heating in parallel bulk current flow. Their work  
668 furthered the understanding of TIs by gaining a comprehension of the mechanism  
669 during the prebreakdown regime, including evidence for bulk dissipation, thermal  
670 activation and possible variable-range hopping. A concurrently reported work by  
671 Gotz et al. also looked to present a metrologically comprehensive measurement of a  
672 TI system (V-doped  $(\text{Bi,Sb})_2\text{Te}_3$ ) in zero magnetic field (Götz et al. 2018). When  
673 they measured the deviation of the quantized anomalous Hall resistance from  $R_K$ ,  
674 they determined a value of  $0.176 \pm 0.25 \mu\Omega/\Omega$ . An example of their data is shown in  
675 Fig. 15c. The steps both works made are vital to our eventual realization of a zero-  
676 field quantum resistance standard.

677 One of the remaining major limitations, besides finding a TI material system with  
678 a large band gap, will be to lift the stringent temperature requirements, which are  
679 currently in the 10 mK to 100 mK range. Fijalkowski et al. show, through a careful  
680 analysis of non-local voltages in devices having a Corbino geometry, that the chiral  
681 edge channels closely tied to the observation of the QAHE continue to exist without  
682 applied magnetic field up to the Curie temperature ( $\approx 20$  K) of bulk ferromagnetism  
683 in their TI system. Furthermore, it was found that thermally activated bulk conduc-  
684 tance was responsible for quantization breakdown (Fijalkowski et al. 2021). The  
685 results give hope that one may utilize the topological protection of TI edge channels  
686 for developing a standard, as has been demonstrated most recently by Okazaki et al.  
687 (2021). They demonstrate a precision of  $10 \text{ n}\Omega/\Omega$  of the Hall resistance quantization  
688 in the QAHE. They directly compared both the QAHE and QHE from a conven-  
689 tional device to confirm their observations. Given this very recent development,  
690 more efforts are expected to follow to verify the viability of TIs as a primary standard  
691 for resistance. In the ideal case scenario, TI-based QHR devices will make dissem-  
692 inating the ohm more economical and portable, and will, more importantly, serve as  
693 a basis for a compact quantum ampere.

## 694 Outlook

695 As the global implementation of new technologies continues to progress, one should  
696 hope to see a more universal accessibility to the quantum SI. This chapter has given  
697 historical context for the role of the QHE in metrology, including a basic overview of  
698 the QHE, supporting technologies, and how metrology research has expanded these  
699 capabilities. The present-day graphene era was summarized in terms of how the new



**Fig. 15** (continued) smaller than the data point. Reprinted figure with permission from (Fox et al. 2018). Copyright 2018 by the American Physical Society. (c) Another series of measurements on a topological insulator at the  $\nu = 1$  plateau. Measurement currents of 5 nA and 10 nA were used in both orthogonal and diagonal configurations. The colored rectangles represent the weighted average and standard deviation of the data from those configurations. (Reprinted from (Götz et al. 2018), with the permission of AIP Publishing)

700 2D material performed compared with GaAs-based QHR devices, how the world  
701 began to implement it as a resistance standard, and how the corresponding measure-  
702 ment infrastructure has adapted to the new standard. In the third section, emerging  
703 technologies based on graphene were introduced to give a brief overview of the  
704 possible expansion of QHR device capabilities. These ideas and research avenues  
705 include *pnJ* devices, QHARS devices, and experimental components of AC metrology  
706 and the quantum ampere. The chapter then concludes by discussing the possible  
707 limitations of graphene-based technology for resistance metrology and looks to  
708 explore TIs as one potential candidate to, at the very least, supplement graphene-  
709 based QHR devices for resistance and electrical current metrology.

710 It has become evident throughout the last few decades that the quantum Hall  
711 effect, as exhibited by our modern 2D systems both with and without magnetic  
712 fields, has the marvelous potential to unify the components of Ohm's  $V = IR$  relation.  
713 That is, to bring together all three electrical quantities allowing several traceability  
714 capabilities will undoubtedly improve electrical metrology worldwide. Throughout  
715 all the coming advancements, it will be important to remember that these milestones  
716 should keep us motivated to continue learning how to better enrich society with the  
717 quantum Hall effect:

AU5  
AU6

718 It is characteristic of fundamental discoveries, of great achievements of intellect, that they  
719 retain an undiminished power upon the imagination of the thinker. – Nikola Tesla, 1891,  
720 New York City, New York

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725 endorsement by the National Institute of Standards and Technology or the United States govern-  
726 ment, nor is it intended to imply that the materials or equipment identified are necessarily the best  
727 available for the purpose.

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